

RAITH

NANOFABRICATION

Raith NanoSuite Tutorials



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Structure of Tutorials

The Tutorials are structured into different Tasks, each task consists of several Steps. Each tutorial has an aim specified at the start of each tutorial, and the tasks will guide you step-by-step through the process of achieving this aim. To set up an exposure you will need to carry out the tutorials 1-4 first before performing the exposure in tutorial 5. It is important to study the tutorials in the given order. Tutorial 6 gives an overview of general pattern designs.

The SEM portion of the system is referred to as the Column Control. The Raith portion of the system is referred to as the Lithography Control.

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